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To: Examiner, Stock

From: Tarik Nabi

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Comments:

Please find synopsis of Amendment as requested.

Thank you,

Sent by: _____

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Tanaka teaches a blind (12) acting as a field stop for adjusting the illuminating area of the illuminating light for the mask (col. 3, lines 13-20; Fig. 1) for projecting the pattern of a photomask (Abstract, lines 1-2). Tanaka does not teach a positional deviation detecting apparatus. Furthermore, the blind (12) in Tanaka is further defined as being equivalent to a shutter mechanism (col. 6, lines 20-24) that opens and closes depending on the level of exposure of a wafer. This function is performed, in Applicant's invention, by the field stop position adjustment mechanism (40, Fig. 1), which is only one part of the image field position adjustment mechanism of Applicant's invention.